

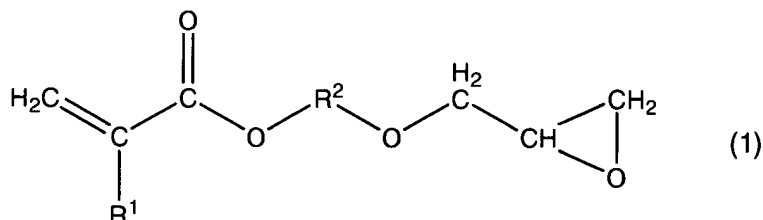
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Claims

1. A photosensitive resin composition characterized by comprising

a poly((meth)acrylic acid)-based water-soluble photosensitive resin (A) having an acid value of 150 mgKOH/g or more on a solid basis;

the resin (A) being formed of a ((meth)acrylic acid)-based polymer in which a compound represented by formula (1):



(wherein R^1 represents H or Me; and R^2 represents a linear or branched C2-C10 alkylene group) has been added to portions of the carboxylic groups,

a photopolymerization initiator (B); and

water (C).

2. A photosensitive resin composition according to claim 1, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are partially or entirely neutralized with an alkali.

3. A method for forming a hydrogel characterized by comprising subjecting a photosensitive resin composition as recited in claim 1 or 2 to photopolymerization.

Statement under Article 19(1)

In amended claim 1, the acid value has been clarified to be 170 mgKOH/g or more on a solid basis.

Each of added claims 4 and 5 claims a hydrogel formed through the method as recited in claim 3.